

**Tutorial, Hot Chips Conference
Stanford University
Sunday, August 18, 2002
Morning Session**

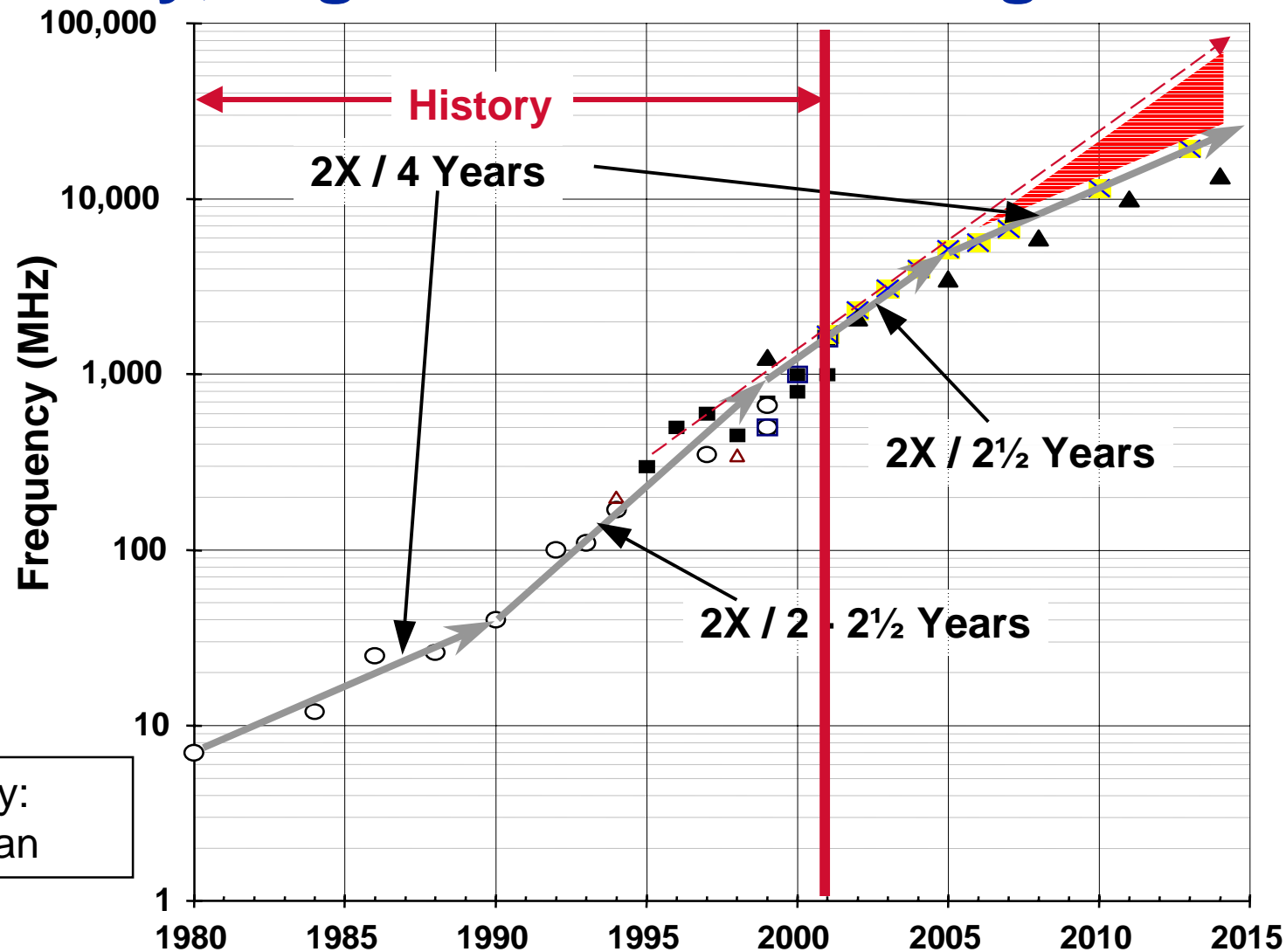
**Overview:
IC Technology Scaling Trends,
Challenges, and Potential Solutions
through the End of the
Semiconductor Roadmap**

**Peter M. Zeitzoff,
International SEMATECH, Austin, TX**

Introduction: Moore's Law

- **IC industry following Moore's Law because of its benefits**
 - Increased speed
 - Lower power dissipation per function
 - Increased transistor and function density
 - Lower cost/function
- **Moore's Law → continuous improvements in design and rapid technology scaling**
 - IC technology rapidly scaling into deep submicron regime (currently, 130nm technology generation).

Moore's Law Scaling of Chip Clock Frequency, High-Performance Logic



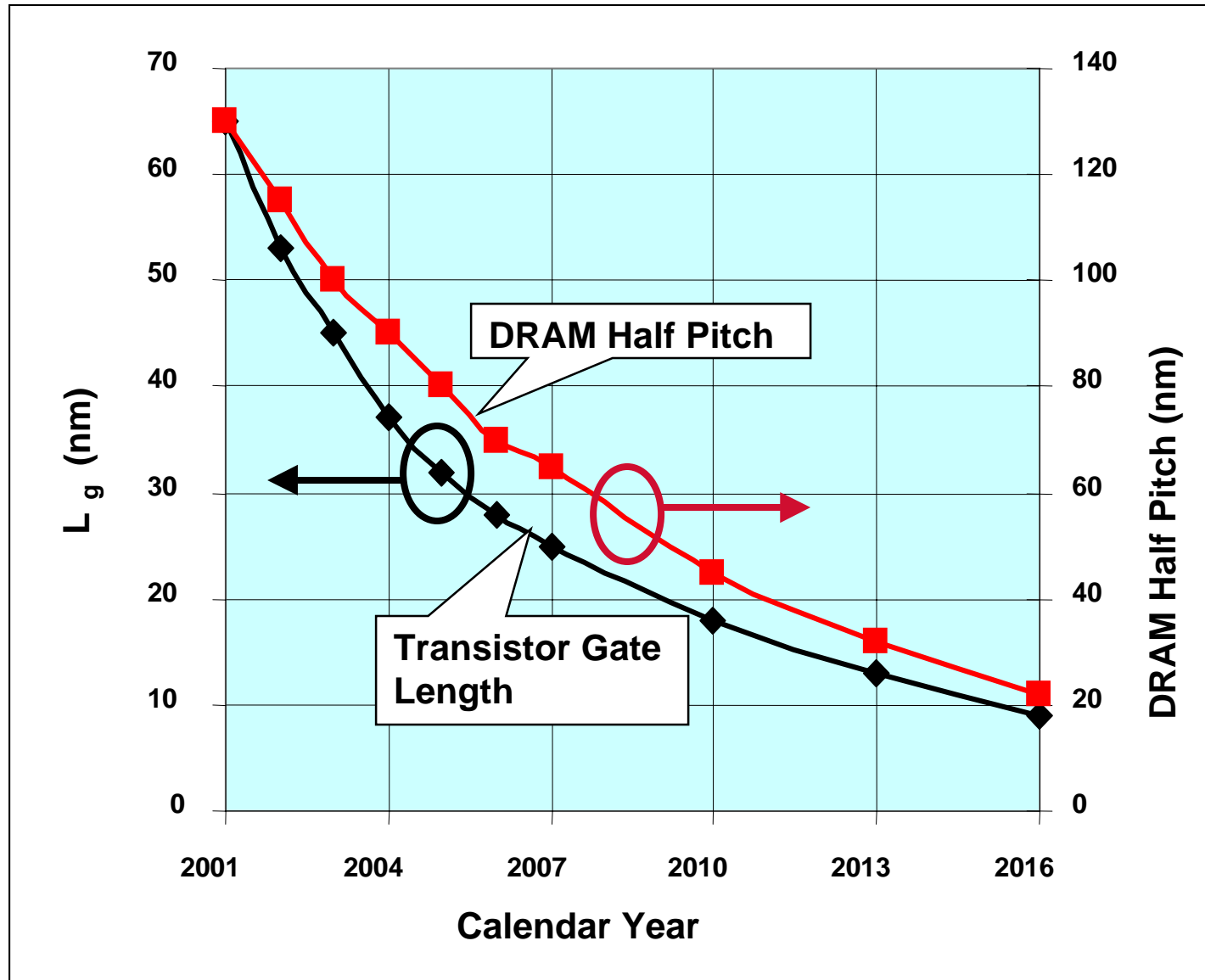
Courtesy:
Alan Allan

Sources: Sematech, 2001 ITRS ORTC

Introduction: Moore's Law

- **IC industry following Moore's Law because of its benefits**
 - Increased speed
 - Lower power dissipation per function
 - Increased transistor and function density
 - Lower cost/function
- **Moore's Law → continuous improvements in design and rapid technology scaling**
 - IC technology rapidly scaling into deep submicron regime (currently, 130nm technology generation).

DRAM Half Pitch and Transistor Gate Length Scaling, 2001 ITRS



IC Technology Scaling and Moore's Law

- The IC industry is committed to follow Moore's law as long as possible to continue to enjoy the benefits
- Scaling of transistors and interconnect drives technology scaling
 - Rapid scaling of lithography resolution is critical to enabling transistor and interconnect scaling
- In this tutorial, we'll discuss:
 - Scaling trends, challenges, and potential solutions in 3 key areas
 - MOSFETs and front-end processing (Dr. Peter Zeitzoff)
 - Interconnect (Dr. Mike Thomas)
 - Lithography (Prof. Alfred Wong)
 - Scaling of MOSFETs, interconnect, and lithography: impact on chip performance, power dissipation, and functional density
 - This technology scaling is the “raw material” that designers work with
 - Design-related concerns regarding lithography scaling
 - Data, CAD, and design rule issues with OPC and PSM
 - Lithography friendly layout

International Technology Roadmap for Semiconductors (ITRS)

- **Industry-wide effort to project the progress of the IC technology generations for the next 15 years**
 - **Provides common reference for semiconductor industry**
- **Goal: aid the industry to continue following Moore's Law**
- **ITRS will be utilized in this tutorial**